

Pattern uniformity control in room-temperature imprint lithography

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Non-uniformity in patterning that can arise in room-temperature imprint lithography is analyzed and a condition is presented under which the uniformity is assured. The condition is developed in such a way that the elastic recovery of stain-hardened polymer after the mold is removed does not cause the non-uniformity. Experimental testing of the condition reveals that it is a reliable criterion for uniform patterning.